

	Hit s	Search Text	DBs
1	6	(substrate or wafer) and ((imag\$4 or photosensitive or photoresist or resist) same expos\$4 same (wavelength or UV) same (hydrophilic\$4 or wettab\$4)) and interference and ((deposit\$4 or coat\$4) same (co\$1polymer\$4 or polymer\$4)) and anneal\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
2	496	((substrate or wafer) same (imag\$4 or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettab\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
3	6	((substrate or wafer) same (imag\$4 or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettab\$4)) and (light same (two or split\$4 or multiple) same beam same (expos\$4 or illuminat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
4	48	((substrate or wafer) same ((organic with polymer) or (poly\$1styrene or PMMA or poly\$1methyl\$1methacrylate or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable or (surface with tension))) and (light same (two or split\$4 or multiple) same beam same (expos\$4 or illuminat\$4))) and interference	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
5	5	((substrate or wafer or carrier) same ((organic with polymer) or poly\$1styrene or PMMA or poly\$1methyl\$1methacrylate or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable)) and (light same (two or split\$4 or multiple) same beam same (expos\$4 or illuminat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
6	18	((substrate or wafer or carrier) same ((organic with polymer) or poly\$1styrene or PMMA or poly\$1methyl\$1methacrylate or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable)) and ((light or laser or illuminat\$4optical) same (two or split\$4 or multiple) same beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
7	18	((substrate or wafer or carrier) same ((organic with polymer) or poly\$1styrene or PMMA or poly\$1methyl\$1methacrylate or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable)) and ((light or laser or illuminat\$4 or optical) same (two or split\$4 or multiple) same (beam or beam\$1splitter))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
8	19	((substrate or wafer or carrier) same ((organic with polymer) or poly\$1styrene or PMMA or poly\$1methyl\$1methacrylate or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable)) and ((light or laser or illuminat\$4 or optical) same (two or split\$4 or multiple or (interference adj pattern\$4)) same (beam or beam\$1splitter))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
9	123	((substrate or wafer) same ((organic with polymer) or (poly\$1styrene or PMMA or poly\$1methyl\$1methacrylate or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable or (surface with tension))) and (light same (two or split\$4 or multiple) same beam same (expos\$4 or illuminat\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
10	1	((substrate or wafer) same ((organic with polymer) or poly\$1styrene or PMMA or poly\$1methyl\$1methacrylate or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable or (surface with tension))) and ((light or laser) same (two or split\$4 or multiple) same (beam or beam\$1splitt\$4) same (interference or (interference with pattern\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	22	((substrate or wafer) same ((organic with polymer) or poly\$1styrene or PMMA or poly\$1methyl\$1methacrylate or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable or (surface with tension))) and ((light or laser) same (two or split\$4 or multiple) same (beam or beam\$1splitt\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
12	1	(substrate or wafer or carrier) and (((organic with polymer) or poly\$1styrene or PMMA or poly\$1methyl\$1methacrylate) same (imageable or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable or (surface with tension))) and ((light or laser) same (two or split\$4 or multiple) same (beam or beam\$1splitt\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
13	4	(substrate or wafer or carrier) and (((organic with polymer) or poly\$1styrene or PMMA or poly\$1methyl\$1methacrylate) same (imageable or photoresist or resist) same (layer or coat\$4 or deposit\$4)) and (expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable or (surface with tension))) and ((light or laser) same (two or split\$4 or multiple) same (beam or beam\$1splitt\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
14	2	((("20030045110") or ("6527964"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

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15	39	(substrate or wafer or carrier) and ((imageable or photoresist or resistor photosensitive or light\$1sensitive) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable)) and ((light or laser) same (two or split\$4 or multiple) same (beam or beam\$1splitt\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
16	23	(substrate or wafer or carrier) and ((imageable or photoresist or resistor photosensitive or light\$1sensitive) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable)) and ((light or laser) same (two or split\$4 or multiple or interference) same (beam or beam\$1splitt\$4)) and (PMMA or poly\$1methyl\$1methacrylate or poly\$1styrene or hydroxy\$1polystyrene)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
17	44	(substrate or wafer or carrier) and ((imageable or photoresist or resistor photosensitive or light\$1sensitive) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable)) and ((light or laser) same (two or split\$4 or multiple or interference) same (beam or beam\$1splitt\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
18	39	(substrate or wafer or carrier) and ((imageable or photoresist or resistor photosensitive or light\$1sensitive) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettability or wettable)) and ((light or laser) same (two or split\$4 or multiple) same (beam or beam\$1splitt\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
19	377 1	(substrate or wafer or carrier) and ((imageable or photoresist or resist or photosensitive or light\$1sensitive) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation)) and ((light or laser or synchronon) same (two or split\$4 or multiple) same (beam or beam\$1split\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
20	967	((substrate or wafer or carrier) same (imageable or photoresist or resist or photosensitive or light\$1sensitive) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV)) and ((light or laser or synchronon) same (two or split\$4 or multiple) same (beam or beam\$1split\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
21	12	((("6458715") or ("6271050") or ("6339010") or ("6040201") or ("5910015") or ("5894159") or ("5889292"))).PN.	USPAT; EPO; JPO; DERWENT; IBM_TDB
22	2	("4743091").PN.	USPAT; EPO; JPO; DERWENT; IBM_TDB
23	1	((interference with pattern) same (Lloyd\$1 with mirror) same (beam with (first or second or double or three or third or multiple)) same fringe) and synchroton and (\$2block with co\$1polymer) and (self\$1assembl\$4 with mono\$1layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
24	1	((interference with pattern) same (Lloyd\$1 with mirror) same (beam with (first or second or double or three or third or multiple)) same fringe) and synchroton	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
25	1	((interference with pattern) same (Lloyd\$1 with mirror) same (beam with (first or second or double or three or third or multiple)) same fringe)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
26	2	(interference same (Lloyd\$1 with mirror) same (beam with (first or second or double or three or third or multiple)) same fringe)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
27	0	((substrate or wafer or carrier) same (imageable or photoresist or resist or photosensitive or light\$1sensitive) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV)) and ((light or laser or synchronton) same (two or split\$4 or multiple) same (beam or beam\$1split\$4) same (bulk near3 lamellar near3 period))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
28	6	((("6428939") or ("6440756") or ("6631648"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
29	0	nanopattern\$4 and ((substrate or wafer) same (imag\$4 or photosensitive or photoresist or resist) same (layer or coat\$4 or deposit\$4) same expos\$4 same (wavelength or UV or light or radiation) same (hydrophilic\$4 or wettab\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
30	0	(\$2block with co\$1polymer) and (self\$1assembl\$4 with mono\$1layer) and alkylsiloxane and octadecylltrichlorosilane	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB